

### ABSTRACT OF THE DISCLOSURE

Sub B1  
Q10

An exhaust apparatus for a process apparatus which processes an object using a process gas includes an exhaust pipe to be connected to an exhaust port of the process apparatus, and a trap mechanism connected to the exhaust pipe, for removing an impurity gas contained in an exhaust gas from the process apparatus. The process is for forming a layer on an object. The process gas reacts to form the layer. A reaction-gas supply mechanism is provided in the exhaust pipe at an upstream of the trap mechanism, for feeding a reaction gas which is reacted with the impurity gas in to exhaust pipe to lower a vapor pressure of the impurity gas. The impurity gas is unprocessed gas or non-reacted process gas which has not reacted to form the layer.

subst. B1

### REMARKS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1-11 and 13-25 are pending in the present application; Claims 8 and 13-17 have been amended; Claim 12 has been cancelled; and Claims 19-25 have been added by the present amendment.

In the outstanding Office Action, the drawings have been objected to; Claims 8, 13 and 17 have been objected to; Claims 8, 13, 14 and 17 have been rejected under 35 U.S.C. § 112, second paragraph; Claims 8, 12 and 17 were rejected under 35 U.S.C. § 102(b) as anticipated by or under 35 U.S.C. § 103(a) as obvious over Horiuchi et al; Claims 8, 12, 14 and 17 were rejected under 35 U.S.C. § 103(a) as unpatentable over Horiuchi et al; and Claims 8 and 12-17 were rejected under 35 U.S.C. § 103(a) as unpatentable over Horiuchi et al and further in view of Iwata et al.